

In the Claims:

1. (withdrawn)
2. (withdrawn)
3. (withdrawn)
4. (withdrawn)
5. (withdrawn)
6. (withdrawn)
7. (cancelled)
8. (cancelled)
9. (cancelled)
10. (cancelled)

02 11 (original) A method of endpoint detection in plasma etching, comprising the actions of:

measuring voltage across a plasma system by measuring a voltage difference across an element that is external to said plasma system; and
stopping etch when said voltage decreases a predetermined amount within a predetermined time.

13 12 (original) The method of Claim 12, wherein said element is a resistor.

15 13 (currently amended) The method of Claim 12, wherein said predetermined amount is a voltage ~~drop~~ change of not less than 5% from a reference voltage and said predetermined time is not less than 3 seconds.

- 2V
GIVE 1003
14. (cancelled)
 15. (cancelled)
 16. (cancelled)
 17. (cancelled)
 18. (cancelled)